

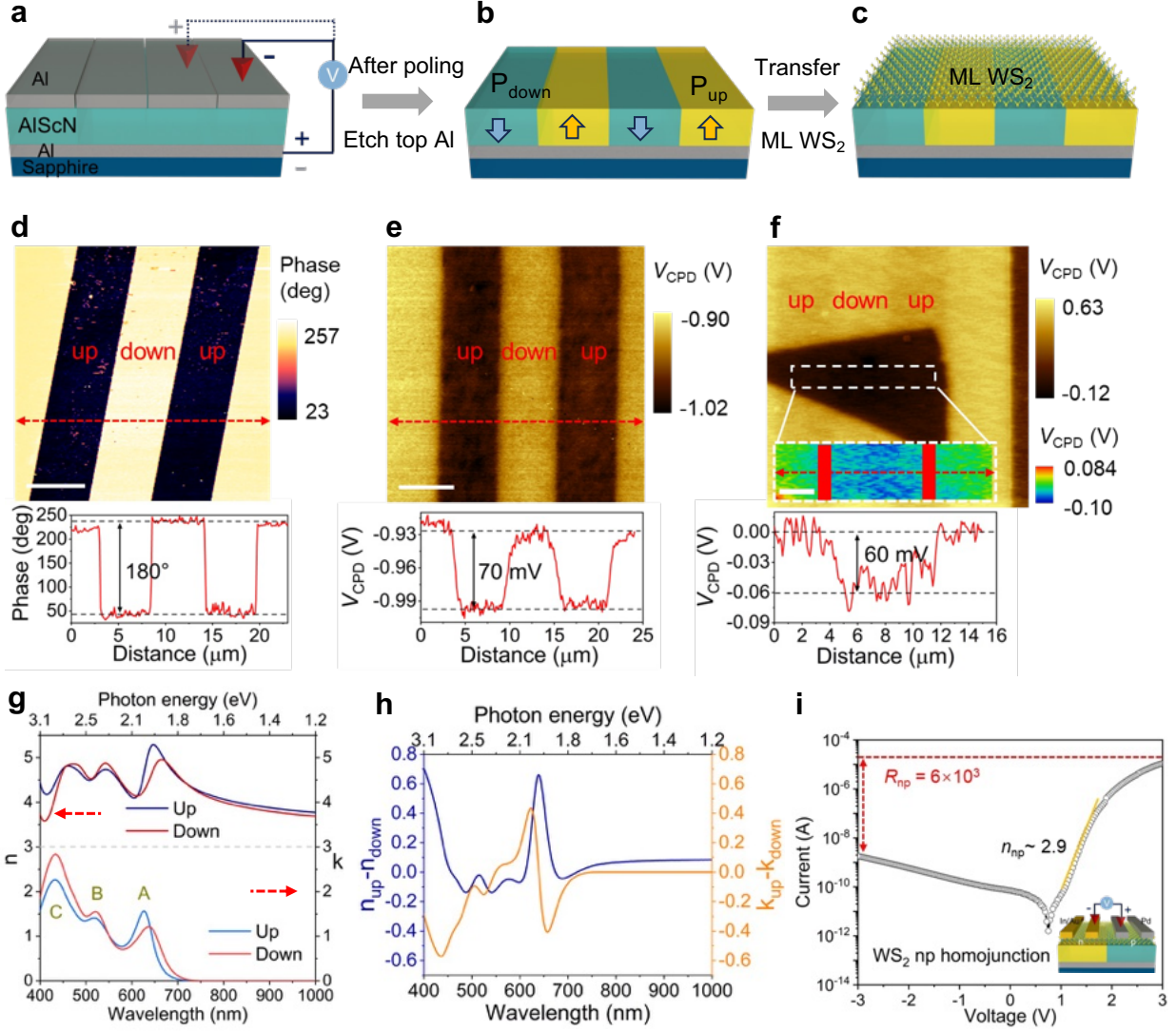


Fig. a, Schematic of AIScN ferroelectric domains locally polarized up and down by applying opposite voltages to the separated Al electrodes. **b**, Schematic of the AIScN pattern after poling and etching Al electrodes. Upward and downward arrows represent AIScN poling up (P_{up}) and down (P_{down}) states, respectively. **c**, Schematic of the ML WS_2 /AIScN device after transferring ML WS_2 onto the patterned AIScN surface with defined polarization domains. **d**, PFM image of the poled AIScN surface. Regions labeled “up” and “down” correspond to P_{up} and P_{down} states, respectively. The bottom curve shows the phase profile along the red dashed line, indicating a 180° phase difference between domains. **e**, SKPM image of the poled AIScN surface. The bottom line profile shows a ~ 70 meV potential difference along the red dashed line on poled AIScN surface. **f**, SKPM image taken of ML WS_2 on the patterned AIScN. The inset shows a zoomed-in view of the white dashed box. The bottom line profile reveals a ~ 60 meV potential difference across the red dashed line on the WS_2 surface. Scale bars, $5\ \mu m$. **g**, Fitted real part n (top) and imaginary part k (bottom) of the refractive index under different polarization states (P_{up} and P_{down}). **h**, Calculated tunable range of optical constants $n_{up}-n_{down}$ (Δn) and $k_{up}-k_{down}$ (Δk) between P_{up} and P_{down} states, demonstrating significant modulation near the A exciton. **i**, Semi-log plot of the I-V curve for the n-p homojunction, with a Shockley diode model fit shown in yellow. The extracted ideality factor is $n_{np} \sim 2.9$, and the rectification ratio at $V = \pm 3$ V is $R_{np} = 6 \times 10^3$.